

**AMENDMENTS TO THE ABSTRACT OF THE DISCLOSURE:**

Kindly replace the Abstract of the Disclosure with the following new Abstract:

The present invention is for supplying supplies a specified quantity  $Q$  of processing gas while dividing at a desired flow rate ratio  $Q1/Q2$  accurately and quickly from a gas supply facility equipped with a flow controller into a chamber. With the present invention, a total quantity  $Q=Q1+Q2$  of gas while dividing is supplied into a chamber  $G$  at a desired flow rate  $Q1$  and  $Q2$  through shower plates ~~3 and 4~~ fixed to the ends of branch supply lines ~~GL1 and GL2~~ by providing open/close valves ~~OV1 and OV2~~ with a plurality of branch supply lines  $GL1$  and  $GL2$ , respectively, to supply the a specified quantity  $Q$  of gas  $G$  from the a gas supply facility ~~equipped with a flow controller QCS into a chamber,~~ and by utilizing a bypass line  $BL1$  on the downstream side of the ~~above-mentioned~~ open/close valve  $OV1$  and branched from  $GL1$ , a bypass line  $BL2$  on the downstream side of the open/close valve  $OV2$  and branched from  $GL2$ , a pressure type division quantity controller ~~FV~~ connected to the bypass line  $BL1$  and the bypass line  $BL2$ , a ~~pressure sensor PS1 to~~ measuring pressure inside the branch supply line  $GL1$ , and ~~another pressure sensor PS2 to~~ measuring pressure inside the branch supply line  $GL2$ .